

Atty. Dkt. No. 039153-0306 (F0793)

**REMARKS**

Applicants respectfully request reconsideration of the present application in view of the foregoing amendments and in view of the reasons which follow.

Claims 7-12 have been amended. Claims 1-6 and 15-20 have been cancelled without prejudice. Claims 21-32 have been added. No new matter is added. After amending the claims as set forth above, Claims 7-14 and 21-32 are now pending in this application.

In paragraphs 1-4 of the Office Action, the present application is subjected to a restriction requirement. The Examiner has restricted the application into Group I (Claims 1-6 and 15-20) and Group II (Claims 7-14). Applicants have cancelled Claims 1-6 and 15-20 without prejudice. Newly added Claims 21-32 are directed toward the subject matter of Group II. Accordingly, Applicants hereby elect the claims of Group II.

In paragraphs 5 and 6 of the Office Action, Claims 7-13 are rejected under 35 U.S.C. § 102(e) as being anticipated by U.S. Patent No. 6,097,361 (Rohner). The Examiner states:

Rohner, in col. 1, lines 8-12, in col. 3, lines 43-63, and in col. 4, lines 1-67, and in col. 5, lines 1-7 discloses a method of manufacturing and integrated circuit comprising providing a pattern of radiation via an LCD assembly and performing a semiconductor fabrication process with a pattern of radiation, and providing a second pattern of radiation via the LCD panel to perform a second semiconductor fabrication with the second pattern of radiation (claims 7-8, and 14). Rohner, in col. 4, lines 9-40, and in col. 6, lines 25-41, discloses that a step-and repeat process is performed to produce the pattern on the light sensitive layer on the substrate (claim 9). Rohner, in col. 1, lines 1-20, discloses that the integrated circuits are produced by patterning layers in succession to form features (metal lines) that comprise elements of an integrated circuit (application specific IC) (claims 10, and 13). Rohner, in col. 10, lines 38-67, and in col. 11, lines 1-10, discloses that the pattern structure is that of a MOS transistor (claim 11). Rohner, in col. 3, lines 61-67, and in col. 4, lines 1-8, and lines 21-25, discloses that the pattern is stored electronically (memory unit configures the LCD display data) (claim 12).

Atty. Dkt. No. 039153-0306 (F0793)

Applicants respectfully traverse the rejection. Rohner is referred to below as the cited art.

Each of the Independent Claims 7, 21 and 27 includes limitations related to the use of a computer data base storing image data. The computer generates component data from the image data to generate the control signal. The present application states:

System 10 can provide ASIC-type functionality by selecting parts from database 34, media storage area 38 or database 42 in accordance with the program to provide images on wafer 12. For example, a software program selecting transistors, diodes, and their interconnections can be executed by computer 32 to cause mask 20 to provide the appropriate structures on wafer 12.

The individual images for the individual parts can be stored in database 34, via the storage unit 38 or database 42. In this way, computer 32 only operates a minimal software program described in integrated circuit (IC). Images for individual components are retrieved from unit 38 or database 42 when needed.

See present application, page 7, line 28 and page 8, line 2. Therefore, the recited method provides significant advantageous related to software efficiency.

The recited methods in Claims 7, 21 and 27 are not shown, described, or suggested in Rohner. Rohner does not disclose, or suggest a method of using a database and component images in a database. Rohner is silent as to how the control signal is generated. Indeed, individual component images and ASIC-functionality are not even mentioned. Therefore, Rohner does not teach every element of Claims 7-12 and 21-32 as recited by 35 U.S.C. § 102(e). Accordingly, Applicants respectfully submit that Claim 7 and its dependent Claims 8-12, Claim 21 and its dependent Claims 22-26 and Claim 27 and its dependent Claims 28-32 are patentable over the cited art.

Applicants believe that the present application is now in condition for allowance. Favorable reconsideration of the application as amended is respectfully requested.

Atty. Dkt. No. 039153-0306 (F0793)

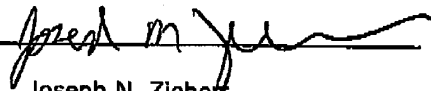
The Examiner is invited to contact the undersigned by telephone if it is f It that  
a telephone interview would advance the prosecution of the present application.

Respectfully submitted,

Date 2.18.03

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